

SPECIFICATION AMENDMENTS

Please amend paragraph [0003] as follows:

[0003] Ellipsometry and reflectometry are powerful techniques for film thickness measurement in semiconductor processing. In cases where the film under examination is transparent to the illuminating radiation, ellipsometry for example can measure films down to one monolayer thick (3 - 10 Angstroms). However, both ellipsometry and reflectometry fail in cases where the film under examination is opaque. Metallic films, which play a major role in integrated circuit fabrication, fall into this category. Optical radiation is absorbed within the first few tens to hundreds of Angstroms of the film, depending on the wavelength. For example, using green radiation at a wavelength of 0.5 micron in aluminum, the absorption length is less than 83 Angstroms. At longer wavelengths, and in particular at infra red wavelengths, this situation gets better, but still ellipsometry cannot provide the full solution with reference to metallic films or other optically opaque films.